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(54) Title: POST-DRY ETCHING PHOTORESIST AND METAL CONTAINING RESIDUE REMOVAL FORMULATION

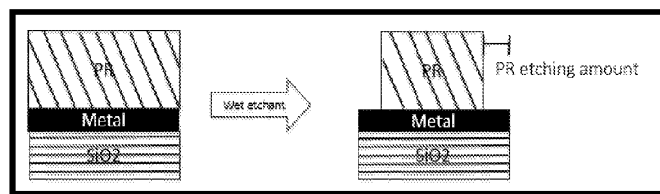


FIG. 1. Photoresist Removal

(57) Abstract: The disclosed and claimed subject matter relates to a stripping composition having a controlled oxide etch and ITO (Indium Tin oxide) etch as well as sidewall polymer and polymer etch residue removal capability and to a process for stripping and etching utilizing the composition.

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